~~What is c~~Claim~~ed is~~:

1. A method for treating a disc-shaped article, comprising:

dispensing a first liquid onto a surface of the disc-shaped article, said first liquid containing at least one inorganic acid at a concentration of at least 90 wt.-%, said first liquid having a fluoride ion concentration of below 10 ppm; and

removing at least part of the first liquid with a second liquid containing at least one inorganic acid at a concentration of above 50 wt.-%, said second liquid having a fluoride ion concentration of above 1 ppm;

wherein the fluoride ion concentration of the second liquid is at least twice that of the first liquid.

2. The method according to claim 1, wherein said second liquid has a fluoride ion concentration of above 10 ppm.

3. The method according to claim 1, wherein the first and second liquids each comprise sulfuric acid.

4. The method according to claim 3, wherein the sulfuric acid of the first liquid is dispensed in the presence of ozone.

5. The method according to claim 4, wherein the third liquid is water.

6. The method according to claim 3, wherein the fluoride ion concentration of the second liquid is above 10 ppm.

~~5.~~7. The method according to claim 1 wherein the second liquid is removed by spin-off or a third liquid; wherein the concentration of inorganic acid of said third liquid is less than a tenth of the concentration of the inorganic acid in the second liquid.

~~6. The method according to claim 4, wherein the third liquid is water.~~

~~7.~~8. The method according to claim 1, wherein the disc-shaped article is rotated during dispensing of the first liquid and the second liquid onto the surface of the disc-shaped article.

~~8.~~9. The method according to claim 1 wherein the second liquid is dispensed onto the disc-shaped article at a temperature of above 60°C.

~~9.~~10. The method according to claim 1 ~~wherin~~wherein the concentration of fluoride ions in the second liquid is below 1000ppm.

~~10.~~11. The method according to claim 1, wherein the first liquid is free of added fluoride ion.

~~11.~~12. The method according to claim 1, wherein the fluoride ion concentration of said second liquid is from 4-500ppm.

~~12. The method according to claim 1, wherein the ride ion concentration of the second liquid is above 10ppm.~~

13. The method according to claim 1, further comprising spinning the disc-shaped article after dispensing the first liquid and before dispensing the second liquid, to remove part of the first liquid from the disc-shaped article.

14. The method according to claim 1, wherein the disc-shaped article is a semiconductor wafer in a process module for single wafer wet processing.

15. The method according to claim 1, wherein the disc-shaped article is a glass disc.

16. The method according to claim 1, wherein the fluoride ion concentration of said second liquid is from 15-200 ppm.

17. The method according to claim 1, wherein the fluoride ion concentration of said

second liquid is from 20-100 ppm.

18. The method according to claim 1, wherein the fluoride ion concentration of said second liquid is about 40 ppm.

19. The method according to claim 1, wherein said second liquid is dispensed so as to contact a silicon oxide layer formed on the disc-shaped article.

20. The method according to claim 19, wherein the disc-shaped article comprises a silicon nitride layer underlying said silicon oxide layer.